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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

ATTY.'S DOCKET: JACQUINOT=7

In re Application of:) Art Unit: 1765
Eric JACQUINOT et al) Examiner: Duy DEO
Appln. No.: 09/427,675) Washington, D.C.
Date Filed: October 27, 1999) Confirmation No. 3607
For: NEW ABRASIVE COMPOSITION...) December 26, 2002

REPLY: AMENDMENT AND REMARKS

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

Replying to the Office Action mailed September 25, 2002, and December 25, 2002, having been a legal holiday, please amend as follows:

IN THE CLAIMS

Add the following new claim:

40. (new) A process for mechanical chemical polishing in the integrated circuits industry, comprising rubbing a layer with a support impregnated with an abrasive liquid composition, wherein said layer comprises one layer of silicon oxide and another layer of silicon nitride, and

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